

#10/Amend E
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ted A. Loxley
Serial No. : 09/490,162
Filed : January 22, 2000
For: PROCESS AND APPARATUS FOR CLEANING SILICON WAFERS
Examiner : V. Simkovic
Group Art Unit : 2812 Confirmation No. 681

Box AF
Assistant Commissioner for Patents
Washington, D.C. 20231

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please note page 4

AMENDMENT AFTER FINAL REJECTION
Request for Correction (37CFR1.105)

Sir:

In connection with the final Office action of October 19, 2001, now on appeal, please amend the above-identified application as follows:

Cancel claims 18, 7, 19, 20, 21, 25, 28, 29 and 31 and rewrite as follows:

| -- ~~18~~. (Amended) In a process of the character described for fabrication of microelectronic devices on silicon wafers wherein microcircuits are formed on the front face of a wafer by a plurality of layering, patterning, doping and heating operations and the wafer is wetted and repeatedly subjected to cleaning, rinsing and drying operations to remove contaminants, the improvement wherein said front face of the process wafer is